

Amendments to the Abstract

Please replace the abstract with the following:

Abstract

~~The invention relates to a~~ A method for depositing a plurality of layers on a substrate using gaseous starting materials, whereby the layers are deposited in one single process chamber in successive process steps. The gas phase composition and/or the substrate temperature is varied without the process chamber being opened in the interim, in such a way that layers of different quality can be deposited successively in one deposition chamber.